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# New analysis of lone-pair binding-energy shifts in photoemission from adsorbed molecules: CO and  $NH_3$  on Cu(100)

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The origin of the differential ionization-potential shifts of the CO  $5\sigma$  and NH<sub>3</sub> 3a<sub>1</sub> lone pairs observed in the photoemission spectra of these molecules chemisorbed on transition-metal surfaces is identified. These shifts are unambiguously shown to arise largely from electrostatic, environmental potential effects. The consequences of interunit charge transfer, donation and back donation, and of intraunit polarization for these differential ionization-potential shifts have been determined using the constrained space orbital variation method. They are found to be smaller than the electrostatic shift due to the superposition of the unperturbed charge distributions of the separated, metal and ligand units. Thus, these differential shifts do not indicate the nature of the adsorbate-metal chemical bond; they may, however, indicate the adsorption geometry. Ab initio Hartree-Fock cluster-model studies of chemisorption at an on-top site for CO/Cu(100) and  $NH<sub>3</sub>/Cu(100)$  have been made, but the results are expected to apply to metal surfaces in general.

## I. INTRODUCTlON

In valence photoemission spectra (PES) of chemisorbed lone-pair ligand molecules, one often observes a large differential shift of the ionization potential (IP) of the lonepair derived orbital with respect to those of the other adsorbate valence orbitals. In gas-phase CO, the  $1\pi$  IP is 2.9 eV larger<sup>1</sup> than the (C lone-pair)  $5\sigma$  IP while for CO adsorbed on transition-metal surfaces [e.g.,  $Ni(100)^2$  and  $Cu(100)^3$ ] the resonances due to CO  $5\sigma$  and  $1\pi$  ionization are at almost the same energy.<sup>2, 3</sup> Thus, one finds a differential shift of the 5 $\sigma$  IP by  $\sim$  3 eV with respect to  $1\pi$  when CO is adsorbed. In contrast, the  $1\pi$  and  $4\sigma$  IP separation does not change between chemisorbed and free  $CO<sup>2,3</sup>$  In the case of NH<sub>3</sub>, the 1e IP of the free molecule is larger by  $\sim 6.0$  eV (Ref. 4) than the (N lone-pair)  $3a_1$  IP; for NH<sub>3</sub> adsorbed on transition-metal surfaces [e.g.,  $Fe(111)^5$  and  $Fe(110)^6$ ], the  $3a_1$ -le IP splitting is smaller,  $\sim$  4.5 eV. There is a differential shift of the NH<sub>3</sub> 3a<sub>1</sub> IP by  $\sim$  1.5 eV with respect to 1e when  $NH<sub>3</sub>$  is adsorbed.

The differential lone-pair IP shifts are usually interpreted as bonding shifts acting on the lone-pair orbital which, as a consequence, is assumed to make a major contribution to the chemisorptive bonding with the metal. This idea has been used for the interpretation of the valence PES of, e.g., the NH<sub>3</sub>/Fe system<sup>5,6</sup> where the NH<sub>3</sub> is believed to adsorb with the N pointing towards the metal surface. Also, Allyn, Gustafsson, and Plummer<sup>2</sup> have concluded, from their PES studies on CO/Ni(100), that the CO—Ni bond arises primarily from a CO  $5\sigma$  metal coupling; in this case, it has been established that CO adsorbs with its internuclear axis perpendicular to the surface and <sup>C</sup> closest to the metal. '

However, recent analyses of the lone-pair molecule-metal interaction,  $8.9$  based on the constrained space orbital varia tion (CSOV) method, have given strong evidence that the coupling of the lone-pair orbital with the metal does not make the dominant contribution to the interaction energy. For CO interacting with simple  $sp$  metals<sup>8</sup> and with Cu (Ref. 9) (which has a filled  $d$  band), donation and covalent bonding of CO  $\sigma$  electrons leads to a rather small energy contribution. In the case of metals with open  $d$  shells, the CO to metal  $\sigma$  donation can become somewhat more important for the interaction energy.<sup>10,11</sup> However, all CO/metal systems studied so far with the CSOV analysis show that metal to CO  $\pi$  donation is energetically more important than CO to metal  $\sigma$  donation (involving the lone-pair  $5\sigma$  orbital). This is in strong contrast to the conventional picture of the COmetal bonding.<sup>2</sup> For NH<sub>3</sub> interacting with simple sp metals<sup>8</sup> and Cu,<sup>9</sup> the binding energy arises largely from electrostati contributions due to the large dipole moment of  $NH<sub>3</sub>$  and from polarization effects; NH<sub>3</sub> to metal  $a_1(\sigma)$  donation, believed to involve the lone-pair  $3a_1$  orbital,  $5,6$  is much less important.<sup>8,9</sup> Furthermore, cluster calculations on AlCC  $(Ref. 12)$  and  $AlNH<sub>3</sub>$  (Ref. 13) show that the lone-pair orbital,  $5\sigma$  for CO and  $3a_1$  for NH<sub>3</sub>, Koopmans' theorem (KT) IP increases monotonically as the Al-ligand distance decreases. This occurs even though the interaction becomes more and more repulsive when the Al-ligand distance is decreased from its equilibrium value. This suggests<sup>12</sup> that the differential lone-pair IP shifts are evidence for the geometry of the molecular adsorption rather than for the nature of the bonding.

In the present paper, we discuss the origin of the differential lone-pair IP shifts of  $CO$  and  $NH<sub>3</sub>$  upon adsorption on the Cu(100) surface. In previous work for CO/Ni(100), we have shown<sup>14</sup> that this differential shift arises almost entirely from initial-state effects. Thus, we focus on the changes of the orbital energies  $\epsilon$  for the ligand-derived valence orbitals in Cu<sub>5</sub>L,  $L = CO$  or NH<sub>3</sub>, clusters which we use to model the on-top site adsorption of  $CO$  and  $NH_3$  on  $Cu(100)$ . These clusters contain one Cu atom, the adsorption site atom, of the first layer of the Cu(100) surface and the four second-layer nearest neighbors of this atom; they are denoted  $Cu<sub>5</sub>(1,4)CO$  and  $Cu<sub>5</sub>(1,4)NH<sub>3</sub>$ , respectively.

At the on-top site, the molecules interact mainly with the adsorption site Cu atom while the second-layer atoms of  $Cu<sub>5</sub>(1,4)$  provide an environment for this atom and lead to a hybridization of its valence  $4s$  electron into  $4s$  and  $4p$  character.<sup>9, 15, 16</sup> This results in a limited description of the  $4sp$ conduction band of Cu metal. However, since the direct interaction between Cu(100) and the ligand largely involves the adsorption site Cu atom, the Cu<sub>s</sub> $(1, 4)$ L clusters give a reasonable representation of the main features of the inreasonable representation of the main features of the interaction.<sup>9, 17–19</sup> The specific values of particular adsorption properties obtained with larger clusters may be different from those obtained with  $Cu<sub>5</sub>L$ , but the general features are the same. This is even true when a smaller, one metal atom, CuL cluster is used.<sup>9</sup>

The electronic states and orbitals of the clusters are calculated using the ab initio Hartree-Fock self-consistent field (SCF), method. The orbital energies  $\epsilon$  represent the frozen orbital, Koopmans' theorem, IP's and contain only initialstate effects. The changes of the  $\epsilon$ 's are followed through the various steps of the constrained variations.<sup>8</sup> First, we freeze the Cu<sub>5</sub> and L orbitals of the separated subunits and examine how the potential due to the  $Cu<sub>5</sub>$  subunit changes the orbital energies of the  $L$  subunit. Then we allow, in separate steps, the various intraunit and interunit charge rearrangements. For both CO and NH<sub>3</sub>, the largest contribution to the differential shift of the lone pair  $\epsilon$  arises at the initial, frozen orbital, CSOV step. This is a conclusive demonstration of the electrostatic, environmental potential origin of the differential shift.

# II. COMPUTATIONAL DETAILS

For both  $CO/Cu(100)$  and  $NH<sub>3</sub>/Cu(100)$ , we consider adsorption at an on-top site directly above a Cu surface atom, with the molecular axis perpendicular to the surface and the  $C(N)$  atom nearest to the metal. The  $Cu(100)$  surface is modeled by the  $Cu<sub>5</sub>(1,4)$  cluster. For  $Cu<sub>5</sub>(1,4)$  and  $Cu<sub>5</sub>(1, 4)L$ ,  $L = CO$ , or NH<sub>3</sub>, the geometry and interatomic distances of the Cu atoms are taken from the bulk fcc crystal.<sup>20</sup> The C-O distance  $d_{C_0} = 2.15$  bohrs, and the Cu-C distance  $d_{Cu-C} = 3.70$  bohrs, used in Cu<sub>5</sub>CO, are very close to the equilibrium bond distances from a multiconfiguration self-consistent field study<sup>17</sup> on Cu<sub>5</sub>CO and are within the errors of the distances obtained from a LEED analysis' for CO/Cu(100). For Cu<sub>s</sub>NH<sub>3</sub>, the NH<sub>3</sub> geometry  $d_{N-H} = 1.89$ bohrs and  $\lt$  HNH = 107.2°, are the optimized Hartree-Fock values for the free molecule, $<sup>8</sup>$  and the Cu-N distance</sup>  $d_{\text{Cu-N}}$ =4.30 bohrs, has been optimized<sup>9</sup> for Cu<sub>5</sub>NH<sub>3</sub>. The electronic structure of  $Cu<sub>5</sub>L$  is obtained from ab initio Hartree-Fock SCF calculations using contracted Gaussian basis sets to describe the molecular orbitals; For the four second-layer Cu atoms, a pseudopotential is used to describe the 28 "core" electrons, and only one electron 4s per atom is treated explicitly. The use of the pseudopotential for the peripheral Cu atoms does not significantly influence the Cu-L interaction; this has been confirmed by comparison with all-electron calculations.<sup>16</sup> Details of the basis sets and pseudopotential parameters are given elsewhere.<sup>9, 16</sup> The  $C_{4V}$  point group symmetry ground state of Cu<sub>5</sub>(1,4)

is found<sup>9,15</sup> to be <sup>2</sup>E (7a<sup>2</sup>lb<sup>2</sup>1b<sup>2</sup> 4e<sup>3</sup>), where the five 4sp valence electrons occupy orbitals  $7a<sup>2</sup>$  and  $4e<sup>3</sup>$ . The addition of CO, with the ground-state configuration  ${}^{1}A_{1}$  (5a ${}^{2}1_{e}^{4}$ ), yields a  ${}^{2}E$  (12a<sub>1</sub> 1b<sub>1</sub> 1b<sub>2</sub> 5e<sup>3</sup>) ground state for Cu<sub>5</sub>CO.

For Cu<sub>5</sub>NH<sub>3</sub>, which has  $C_s$  symmetry, there are two almost degenerate low-lying states,  $^{2}A'$  and  $^{2}A''$ ; these are the two  $C_s$  components of the  $C_{4v}$  <sup>2</sup>E state. We have obtained the variationally optimum orbitals and energies for the average of the  $^{2}A'$  and  $^{2}A''$  states. The Cu<sub>5</sub>L orbitals retain much of their subunit, Cu<sub>5</sub> or ligand, character, hence, the free molecule notation wi11 be used for the orbitals which have dominantly ligand character.

We have used the changes in the ligand-derived orbital energies  $\epsilon$  of Cu<sub>5</sub>L to estimate the origin of the IP shifts. For a closed-shell system,  $-\epsilon$  is the Koopmans' theorem IP where final-state effects due to charge relaxation and screening'4 are neglected. For the ionization of open-shell systems, there are different space and spin coupled final ionic state multiplets. In this case,  $-\epsilon$  gives the unrelaxed IP to a multiplet weighted average of the different final states.<sup>14,21</sup> Since the open-shell  $E$  character of Cu<sub>5</sub> does not represent a feature of the Cu(100) surface, it is reasonable to use the  $-\epsilon$  values for the KT IP's.

The CSOV analysis provides a way to determine the energetic importance of intraunit and interunit charge rearrangements<sup>8,9</sup> for the chemisorption of closed-shell, lone-pai molecules where the covalent bonding is dative.<sup>22</sup> The analysis is performed in several steps. For  $Cu<sub>5</sub>L$ , it starts from the interaction of the fixed orbitals of the separated units, Cu<sub>5</sub> and L, placed at the geometry of Cu<sub>5</sub>L. In step  $A$ , denoted FO (frozen orbital), the orbitals of the  $L$  subunit are fixed from the free ligand and the  $Cu<sub>5</sub>$  orbitals, orthogonalized to those of  $L$ , are also fixed (frozen). In step  $\overline{B}$ , denoted FD (frozen density), the densities of both  $L$  and Cu<sub>5</sub> are kept fixed, but the closed-shell occupied orbitals within each subunit are allowed to mix with each other. The Cu<sub>5</sub>L total energies of steps A and B are identical, but the orbital energies can be different. In step 1, denoted  $V(Cu_5; Cu_5)$ , the ligand density is fixed while the orbitals arising from  $Cu<sub>5</sub>$  are allowed to vary in the space of the Cu centered virtual orbitals. This step describes the polarization of the metal charge within the metal space in response to the presence of the (frozen) ligand. In step 2,  $V(Cu<sub>5</sub>, all)$ , the ligand density is still fixed, but the variational space of the  $Cu<sub>5</sub>$  orbitals is increased to include the ligand virtual orbitals. Charge donation from Cu<sub>5</sub> to  $L$ , and the formation of dative covalent bonds is now possible. In step 3,  $V(L;L)$ , the (polarized) Cu<sub>s</sub> charge density of step 2 is fixed, and the ligand-derived orbitals are allowed to vary in the ligand virtual space. Thus, the ligand charge can polarize in response to the presence of the (polarized)  $Cu<sub>5</sub>$ subunit. Finally, in step 4,  $V(L;$ all), the variational space of the ligand orbitals is increased to include the virtual  $Cu<sub>5</sub>$ orbitals, and ligand to metal charge donation is allowed. The similarity of the CSOV step 4 results with those from an unconstrained  $Cu<sub>5</sub>L$  wave function shows the extent to which the important bonding effects have been included (for further details of the CSOV method, see Refs. 8 and 9). Limited tests $^{23}$  have been performed for the constrained variation first of the orbitals arising from the CO unit followed by the variation of the orbitals arising from the metal atoms; in effect, CSOV steps 3 and 4 are performed before steps 1 and 2. The contribution of any particular CSOV step to the interaction energy between metal and CO is very similar for both sequences of steps. It is reasonable to expect that this will also be true for the contributions of the CSOV steps to the Koopmans' theorem IP's.

## III. RESULTS AND DISCUSSIONS

In earlier cluster model studies<sup>14</sup> of CO/Ni(100), the initial- and final-state contributions to the IP shifts of chemisorbed CO have been obtained. Among the CO  $4\sigma$ ,  $5\sigma$ , and  $1\pi$  orbitals, the contribution to the final-state relaxation energy due to the presence of the metal varied by  $\approx 0.25$ eV. In contrast, the FO IP shift for the  $5\sigma$  orbital was larger by  $\approx$  2.0 eV compared to the  $4\sigma$  and  $1\pi$  shifts. Cluster-model studies<sup>24</sup> of NH<sub>3</sub> on Ni and Fe show a similar behavior. The final-state, relaxation, contributions to the IP shifts for the  $2a_1$ ,  $3a_1$ , and 1e orbitals differ by only  $\approx 0.1$ eV, whereas the initial-state, frozen-orbital, contribution to the 3a<sup>1</sup> IP shift is larger by  $\approx 1.0$  eV with respect to those of  $2a_1$  and 1e. Obviously, the differential lone-pair IP shifts are mostly due to initial-state effects and we can use the changes in the KT IP's,  $-\epsilon$ , to determine their origin.

Table I lists our results. For  $Cu<sub>5</sub>CO$  [Table I(a)] and  $Cu<sub>5</sub>NH<sub>3</sub>$  [Table 1(b)], the changes between the KT IP's of the valence-level ligand-derived cluster orbitals in  $Cu<sub>5</sub>L$  and those of the free molecule  $\Delta \epsilon$  are listed for all CSOV steps. The change for the  $n\lambda$  orbital is defined as

$$
\Delta \epsilon(n\lambda) = -\epsilon (C u_5 L, n\lambda) + \epsilon (L, n\lambda) \quad , \tag{1}
$$

where  $\Delta \epsilon > 0$  corresponds to a larger KT IP for the cluster than for the free molecule. The differences between the KT IP's for CO  $1\pi$  and  $5\sigma$ , and for NH<sub>3</sub> 1e and  $3a_1$  are given for comparison. The interaction energy,  $E_{int}$ , between Cu<sub>s</sub> and L is defined as

$$
E_{\text{int}} = E_{\text{SCF}}(Cu_5) + E_{\text{SCF}}(L) - E_{\text{SCF}}(Cu_5L) \quad , \tag{2}
$$

where  $E_{SCF}(X)$  is the total SCF energy of unit X. Positive values of  $E_{\text{int}}$  correspond to bonding, and negative values to repulsion.

For free CO, the  $1\pi$  KT IP is 2.3 eV larger than the  $5\sigma$ . IP; this is somewhat different from experiment due to the neglect of electron correlation and final-state relaxation.<sup>14</sup> When the frozen CO and  $Cu<sub>5</sub>$  orbitals are placed together, step A, the CO IP's shift to larger values. While the  $4\sigma$  and  $1\pi$  shift is 0.9 eV, the  $5\sigma$  shift is dramatically larger, 4.6 eV. This leads to the  $5\sigma$  IP being larger than the  $1\pi$  IP by 1.4 eV, while the  $4\sigma \text{-} 1\pi$  separation is not changed significantly from free CO. These changes in the  $\epsilon$ 's are of purely electrostatic origin; the rigid CO orbitals "see" the potential of the (rigid) Cus charge distribution. Covalent chemical bonds cannot be formed at this CSOV step. Since the CO  $5\sigma$  orbital is directed toward the nucleus of the adsorption site atom, it signficantly overlaps and interpenetrates the Cu charge; to a lesser extent, this also occurs for the other CO orbitals. Thus, the CO  $\epsilon$ 's become smaller, more negative, because their penetration of the Cu charge means that the Cu nucleus is not fully screened; the effect is largest for the  $5\sigma$  orbital. The charge interpenetration also leads to a repulsion between CO and Cu<sub>5</sub> of  $E_{int} = -0.52$  eV. In the frozen density step B, a mixing of the occupied CO  $\sigma$  orbitals is allowed and results in a small 0.4 eV change of the  $4\sigma$  and  $5\sigma \epsilon'$ s, which leaves the  $5\sigma$  KT IP larger than the  $1\pi$  IP.

The Cu<sub>5</sub> charge polarization in  $V(Cu_5; Cu_5)$  does not

TABLE I. Results of the CSOV analysis for (a)  $Cu<sub>5</sub>CO$  and (b)  $Cu<sub>5</sub>NH<sub>3</sub>$ . For the definition of the interaction energies,  $E_{int}$ , and IP shifts,  $\Delta \epsilon$ , see text. The IP separations are given for comparison. All energies are in eV.

	(a) $Cu5CO$ results				
	$E_{\rm int}$	$\Delta \epsilon (4\sigma)$	$\Delta \epsilon(1\pi)$	$\Delta \epsilon (5\sigma)$	$-\epsilon(1\pi)+\epsilon(5\sigma)$
Free CO calc.	$\sim$ $\sim$ $\sim$	21.71 <sup>a</sup>	17.48 <sup>a</sup>	15.19 <sup>a</sup>	$+2.29$
Step A, FO	$-0.52$	0.93	0.89	4.60	$-1.42$
Step B, FD	$-0.52$	1.30	0.89	4.22	$-1.05$
Step 1, $V(Cu_5; Cu_5)$	$-0.28$	1.26	0.83	4.21	$-1.09$
Step 2, $V(Cu_5; all)$	$+0.07$	0.59	0.14	3.54	$-1.12$
Step 3, $V(CO;CO)$	$+0.27$	0.96	0.66	3.60	$-0.66$
Step 4, $V(CO; all)$	$+0.42$	1.06	0.76	3.70	$-0.64$
Cu <sub>5</sub> CO SCF	$+0.45$	0.92	0.87	3.15	$+0.01$
$CO/Cu(100)$ expt.	$-0.7b$	$\cdots$	$\cdots$	$\mathbf{r}=\mathbf{r}+\mathbf{r}$	$-0.0c$
Free CO expt.	$\mathbf{r}=\mathbf{r}+\mathbf{r}$	$\cdots$	.	$\cdots$	2.9 <sup>d</sup>
		(b) $Cu5NH3$ results			
	$E_{\rm int}$	$\Delta \epsilon(2a_1)$	$\Delta \epsilon (1e)$	$\Delta \epsilon (3a_1)$	$-\epsilon(1e) + \epsilon(3a_1)$
Free $NH_3$ calc.	$\mathbf{r}=\mathbf{r}+\mathbf{r}$	31.27 <sup>a</sup>	17.17 <sup>a</sup>	$11.40^a$	$+5.78$
Step $A$ , FO	$+0.55$	1.12	1.05	2.60	$+4.23$
Step $B$ , FD	$+0.55$	1.14	1.05	2.58	$+4.25$
Step 1, $V$ $Cu5$ ; $Cu5$ )	$+0.70$	1.55	1.45	3.09	$+4.14$
Step 2, $V(Cu_5; all)$	$+0.72$	1.55	1.44	3.09	$+4.13$
Step 3, $V(NH_3; NH_3)$	$+0.80$	1.50	1.46	2.85	$+4.38$
Step 4, $V(NH_3; all)$	$+0.91$	1.69	1.64	2.97	$+4.45$
Cu <sub>1</sub> NH <sub>3</sub> SCF	$+0.92$	1.77	1.74	3.21	$+4.30$
$NH3/Cu(100)$ expt.	$-0.7e$	$\mathbf{a}=\mathbf{a}+\mathbf{a}$	$\cdots$	$\mathbf{r}=\mathbf{r}+\mathbf{r}$	$-4.5$ <sup>f</sup>
Free NH <sub>3</sub> expt.	$\cdots$	$\cdots$	$\cdots$	$\cdots$	6.08

'Koopmans' theorem IP's,

 $-\epsilon(n\lambda)$ , for the free molecule.

bSee Ref. 28. 'See Ref. 3.

dSee Ref. 1. 'See Ref. 29. <sup>f</sup>Experiments for  $NH<sub>3</sub>/Fe$ ; see Refs. 5 and 6. See Ref. 4.

modify the  $\epsilon$ 's significantly, although the repulsion between  $Cu<sub>5</sub>$  and CO is decreased by 0.23 eV. When charge transfer from Cu<sub>5</sub> to CO is allowed in  $V$ (Cu<sub>5</sub>, all), the Cu<sub>5</sub>-CO interaction increases by 0.35 eV and becomes attractive; this is mainly due to Cu<sub>5</sub> to CO  $\pi$  donation.<sup>9</sup> The  $\pi$  charge transfer leads to an effective negative charge on the CO. All CO valence-level IP's,  $-\epsilon$ , decrease by 0.7 eV. It is easier to remove an electron  $CO^{x-}$  than from neutral CO. However, the change in the IP separations is small at this CSOV step. In  $V(CO; CO)$ , the CO charge polarizes to respond to the presence of the (polarized) Cu<sub>5</sub>. As a result, the CO  $\epsilon$ 's become more negative by 0.1-0.5 eV; the  $5\sigma$ FO IP is still larger than the  $1\pi$  IP, but only by 0.7 eV. In the final CSOV step,  $V(CO;all)$ , charge transer from CO to Cu<sub>5</sub>, almost entirely  $\sigma$  donation,<sup>9</sup> is included and leads to a rather small increase in  $E_{int}$ ; the FO IP's of  $4\sigma$ ,  $5\sigma$ , and  $1\pi$ are uniformly increased by 0.<sup>1</sup> eV. The results of this step are rather close to those of the unconstrained  $Cu<sub>5</sub>CO$  SCF calculation.  $E_{int}$  differs by only 0.03 eV which confirms that the CSOV sequence contains the major contributions to the  $Cu<sub>5</sub>-CO$  interaction. There are somewhat larger differences in the  $\epsilon$ 's 0.1–0.5 eV, between the last CSOV step and the full SCF. In part, these differences arise because the orbital energies are more sensitive to small changes in the charge distribution than is the total energy, They also arise because in the full SCF there is a mixing of the occupied orbitals of the Cu<sub>5</sub> and CO subunits with each other;<sup>12,25</sup> this mixing is not allowed in our sequence of CSOV steps. It is not important for the total energy of the neutral  $Cu<sub>5</sub>CO$ cluster as is clearly shown by the near agreement of  $E_{int}$  for the  $V(CO;all)$  CSOV step and for the full SCF. However, preliminary results from a study of final, ionic, state effects<sup>25</sup> show that this mixing does contribute to the IP's. The difference between the  $5\sigma$  and  $1\pi$  IP shifts changes somewhat for the various CSOV steps, from 3.7 eV at the FO superposition, CSOV step  $A$ , to 2.3 eV for the unconstrained SCF calculation. However, the large FO value clearly shows the dominant electrostatic origin of the differential shift.

The results for ammonia ionization are qualitatively very similar to those for CO. The  $1e$  KT IP of free NH<sub>3</sub> is 5.8 eV larger than the  $3a_1$  IP; this is close to the experimental difference,  $\approx 6.0$  eV (Ref. 4). The superposition of the frozen  $NH_3$  and Cu<sub>5</sub> orbitals, CSOV step A, leads to an increase of the NH<sub>3</sub> IP's which is about the same for the  $2a_1$ and 1e orbitals, 1.1 eV, but considerably larger for  $3a_1$ , 2.60 eV. As a consequence, the  $1e-3a_1$  IP splitting of the free molecule is reduced by 1.5 eV. The change is due to different electrostatic effects for the  $3a_1$  orbital compared to  $1e$ or  $2a_1$ . The  $3a_1$  N lone pair is directed towards the absorption site Cu atom and penetrates into the Cu charge to a much larger extent than the  $NH<sub>3</sub> 2a<sub>1</sub>$  and le orbitals, which are localized between N and H in the molecule. In contrast to Cu<sub>5</sub>CO, the charge superposition of  $NH<sub>3</sub>$  and Cu<sub>5</sub> results in an attraction,  $E_{int} = +0.55$  eV, which can be explained by the large NH<sub>3</sub> dipole moment and its orientation  $(N-H_3^+)$ with respect to  $Cu<sub>5</sub>.<sup>8,9,26</sup>$  When mixing of the occupied NH<sub>3</sub>  $a_1$  orbitals is allowed, step B, the  $2a_1$  and  $3a_1$  KT IP values are only very slightly modified.

The Cu<sub>5</sub> charge polarization at step  $V(Cu_5; Cu_5)$  leads to an increase of all  $NH<sub>3</sub>$  derived valence IP's by about the same amount, 0.4-0.5 eV. These shifts are considerably larger than the corresponding shifts for  $Cu<sub>5</sub>CO$ , which is explained by the increased  $Cu<sub>5</sub>$  charge rearrangement<sup>9</sup> in the presence of the large NH<sub>3</sub> dipole moment. However, the binding-energy contribution due to  $Cu<sub>5</sub>$  polarization is found to be somewhat smaller in  $Cu<sub>5</sub>NH<sub>3</sub>$ , 0.15 eV, than in Cu<sub>5</sub>CO, 0.24 eV. Charge transfer from Cu<sub>5</sub> to NH<sub>3</sub>, included in  $V$ (Cu<sub>5</sub>, all), has only a minor influence on both  $E_{int}$ and the  $NH<sub>3</sub>$  IP shifts; this is expected since there is no significant metal to ammonia donation. <sup>9</sup> Polarization of the NH<sub>3</sub> in response to the (polarized) Cu<sub>5</sub>,  $V(NH_3; NH_3)$ , which increases the binding by 0.08 eV, results in changes of the  $\Delta \epsilon$  values by very small amounts for  $2a_1$  and le, 0.02-0.05 eV, while the effect on  $\Delta \epsilon(3a_1)$  is larger, 0.24 eV, but still small. The last CSOV step,  $V(NH_3; all)$ , includes, in addition,  $NH<sub>3</sub>$  to Cu<sub>5</sub> donation involving the lone-pair  $3a_1$  orbital.<sup>9</sup> This increases the binding by 0.11 eV; the  $NH<sub>3</sub>$  derived valence IP's increase by 0.1-0.2 eV. The  $Cu<sub>5</sub>NH<sub>3</sub>$  binding energy at the last CSOV step is, as in  $Cu<sub>5</sub>CO$ , very close to the unconstrained SCF result which confirms the validity of the energy decomposition. The differential lone-pair  $3a_1$  IP shift of  $\approx 1.5$  eV in NH<sub>3</sub>, which arises already in the frozen orbital superposition (step  $A$ ), varies by less than 0.2 eV among the CSOV steps. This confirms its electrostatic origin.

### IV. CONCLUSION

The present study on  $Cu<sub>5</sub>(1,4)CO$  and  $Cu<sub>5</sub>(1,4)NH<sub>3</sub>$ clearly demonstrates the dominant electrostatic contribution to the observed differential lone-pair IP shifts for chemisorbed  $CO$  and  $NH<sub>3</sub>$ . The separations between the  $CO$ derived valence orbital IP's in  $Cu<sub>5</sub>CO$ , computed in the KT approximation, reproduce the experimental findings;<sup>3</sup> the  $1\pi$ -4 $\sigma$  IP separation remains almost constant between free CO and the adsorbed molecule, while the  $5\sigma$ -1 $\pi$  IP separation is drastically reduced. Preliminary results<sup>27</sup> for a much larger  $Cu_{29}CO$  cluster give essentially identical changes in the CO  $\epsilon$ 's for CSOV steps 1-4. The similarity in the  $\Delta \epsilon$ results for  $Cu<sub>5</sub>CO$  and  $Cu<sub>29</sub>CO$  is very strong evidence that our conclusions are indeed valid for chemisorbed CO. For  $NH<sub>3</sub>$ , the differential  $3a<sub>1</sub>$  IP shift is also of dominantly electrostatic origin. The separations between the KT IP's of the  $NH<sub>3</sub>$  derived valence orbitals in Cu<sub>5</sub>NH<sub>3</sub> are consistent with experimental results for  $NH<sub>3</sub>$  on transition metals, e.g., iron.<sup>5,6</sup> The  $3a_1$ -le separation is reduced by  $\approx 1.5$  eV between free NH<sub>3</sub> and the adsorbed molecule, while the  $1e^{-2}a_1$  separation remains constant. Even though the importance of the electrostatic potential effect has been demonstrated for Cu(100), it should also be important for demonstrated for Cu(100), it should also be important for<br>other metals.<sup>12,13</sup> In the case of open  $d$ -shell metals, where the ligand to metal  $\sigma$  donation is somewhat more important,  $^{10,11}$  there may also be shifts due to dative  $5\sigma$ -d bonding. However, these will occur in addition to the electrostatic effects which we have shown to be important.

Our results unambiguously show that the differential lone-pair IP shift does not measure the nature of the dative covalent bonding. On the other hand, the shift does show that the adsorption geometry has the lone-pair orbital directed toward the surface.<sup>12</sup> The magnitude of the shift may be a measure of the distance between the adsorbate and the a measure of th<br>metal surface.<sup>12,11</sup>

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